ORGANIC CHEMISTRY

FRONTIERS







View Article Online
View Journal | View Issue

RESEARCH ARTICLE



Cite this: *Org. Chem. Front.*, 2017, **4**, 1917

Fe-Catalyzed insertion of fluoromethylcarbenes generated from sulfonium salts into X-H bonds (X = Si, C, P)†

Yaya Duan, Da Jin-Hong Lin, D*a Ji-Chang Xiao*a and Yu-Cheng Gub

Received 1st June 2017, Accepted 19th June 2017 DOI: 10.1039/c7qo00430c

rsc.li/frontiers-organic

The Fe-catalyzed insertion of fluoromethylcarbenes including trifluoromethylcarbene and difluoromethylcarbene generated *in situ* from sulfonium salts ($Ph_2S^+CH_2CF_3^-OTf$ and $Ph_2S^+CH_2CF_2H^-OTf$) into X–H (X = Si, C and P) bonds is described. The insertion of both carbenes into the Si–H bond occurred smoothly, and trifluoromethylcarbene could also insert into C–H and P–H bonds.

Fluoromethylcarbenes, including trifluoromethylcarbene $(CF_3CH:)^1$ and difluoromethylcarbene $(HCF_2CH:)^2$ have proven to be attractive synthetic tools for the incorporation of trifluoromethyl (CF_3) and difluoromethyl (HCF_2) fragments, both of which are valuable functionalities in medicinal chemistry, materials chemistry, and so on. Although X–H bond (X = C, Si, etc.) functionalization has received a great deal of attention due to its high efficiency and atom economy, and significant efforts have been directed toward the development of efficient methods for the insertion of carbenes into the X–H bond, the insertion of fluoromethylcarbenes into the X–H bond remains challenging.

Trifluoromethyldiazomethane (CF₃CHN₂)^{1d,g,6} and difluoromethyldiazomethane (HCF₂CHN₂)^{2,7} have served as versatile intermediates in a variety of transformations. It was recently found that they can act as a trifluoromethylcarbene precursor¹ and a difluoromethylcarbene precursor,² respectively. But the insertion of fluoromethylcarbenes into the X–H bond has been limited to CF₃CHN₂. ^{1h-j} In 2012, the group of Ma reported that the Cu-catalyzed insertion of trifluoromethylcarbene produced from CF₃CHN₂ into the Csp–H bond occurred smoothly to afford the desired product in high yields. ^{1h} In 2015, Wang and co-workers described the insertion into N–H and O–H bonds catalyzed by a silver complex. ¹ⁱ Shortly afterwards, Gouverneur *et al.* found that the insertion strategy could be successfully applied to Si–H, B–H, P–H, S–H, and N–H bonds. ^{1j} Apparently,

Si, P, *etc.*). However, it is a potentially explosive and toxic gas, limiting its synthetic utility. Therefore, the development of mild protocols for the insertion of fluoromethylcarbenes into X–H bonds is highly desirable.

We have shown that fluorinated carbenes can be produced.

 CF_3CHN_2 is efficient for the insertion into X-H bonds (X = C,

We have shown that fluorinated carbenes can be produced from fluorinated ylides including phosphonium ylides⁸ and sulfonium ylides⁹ under mild conditions. On the basis that trifluoromethyl sulfonium ylide (Ph₂S⁺CH⁻CF₃) and difluoromethyl sulfonium ylide (Ph₂S⁺CH⁻CF₂H) could be converted by FeCl (TPP) into trifluoromethylcarbene (Fe=CHCF₃)^{9a} and difluoromethylcarbene (Fe=CHCF₂H), ^{9c} respectively, we have now investigated the use of both sulfonium ylides as fluoromethylcarbene precursors in the insertion into X-H bonds (X = Si, C, and P). Ylides Ph₂S⁺CH⁻CF₃ and Ph₂S⁺CH⁻CF₂H were *in situ* generated from sulfonium salts Ph₂S⁺CH₂CF₃ TOTf (I) and Ph₂S⁺CH₂CF₂H TOTf (II), respectively, *via* deprotonation by CsF.

We previously found that a reductant was not required in the Fe-catalyzed transformation of trifluoromethylcarbene, 9a but it was necessary in the reaction of difluoromethylcarbene.9c Interestingly, in the Fe-catalyzed insertion of trifluoromethylcarbene into the Si-H bond in DMA, the presence of the reductant Na₂S₂O₄ could slightly increase the yield (Table 1, entry 3 vs. 1). A comparable yield was obtained in DMF (entry 4). Increasing the loading of salt I and CsF could lead to the increase in the yields (entries 6-8 vs. 3). The yield was further increased slightly by increasing the amount of the catalyst FeCl(TPP) (TPP = 5,10,15,20-tetraphenyl-21H,23H-porphine) from 1 mol% to 2 mol% (entry 9 vs. 8). However, 3 mol% of catalyst loading did not increase the yield (entry 10 vs. 9). The absence of the reductant Na2S2O4 resulted in a lower yield (entry 11 vs. 9). Room temperature was found to be the appropriate reaction temperature. Irrespective of whether the temperature was elevated or lowered, the yields were decreased (entries 12-14 vs. 9).

^aKey Laboratory of Organofluorine Chemistry, Shanghai Institute of Organic Chemistry, University of Chinese Academy of Sciences, Chinese Academy of Sciences, 345 Lingling Road, Shanghai 200032, China. E-mail: jchxiao@sioc.ac.cn, jlin@sioc.ac.cn; Tel: +86-21-54925340, (+86)21-5492-5541

^bSyngenta, Jealott's Hill International Research Centre, Bracknell, Berkshire RG42 6EY, UK

 $[\]dagger \, Electronic$ supplementary information (ESI) available. See DOI: 10.1039/c7qo00430c

Research Article

Table 1 Optimization of reaction conditions for the insertion into the Si-H bond^a

Et	₃ Si-H + Ph ₂ S⁺CH ₂ CF ₃ *OT:	_red	CI(TPP) (x mol %) uctant (20 mol %) sF, DMA, rt, 2 h	Et ₃ SiCH ₂ CF ₃ 2a
Entry	Reductant	х	Ratio ^b	Yield ^c (%)
1	_	1	1:1:1.1	41
2	Zn	1	1:1.1:1.2	43
3	$Na_2S_2O_4$	1	1:1.1:1.2	50
4^d	$Na_2S_2O_4$	1	1:1.1:1.2	45
5	$Na_2S_2O_4$	1	1.3:1:1.2	56
6	$Na_2S_2O_4$	1	1:1.3:1.5	66
7	$Na_2S_2O_4$	1	1:1.5:1.8	70
8	$Na_2S_2O_4$	1	1:2:2.5	79
9	$Na_2S_2O_4$	2	1:2:2.5	83
10	$Na_2S_2O_4$	3	1:2:2.5	81
11	_	2	1:2:2.5	70
12^e	$Na_2S_2O_4$	2	1:2:2.5	53
13^f	$Na_2S_2O_4$	2	1:2:2.5	45
14^g	$Na_2S_2O_4$	2	1:2:2.5	64

^a Reaction conditions: 1a (0.2 mmol), sulfonium salt I, FeCl(TPP), reductant, and CsF in DMA (1.5 mL) at rt for 2 h. b Molar ratio of 1a: salt I: CsF. ^c The yields were determined by ¹⁹FNMR. ^d DMF was used as the reaction solvent instead of DMA. ^eThe reaction temperature was 40 °C. ^fThe reaction temperature was 50 °C. ^gThe reaction temperature was 0 °C.

With the optimal reaction conditions in hand (Table 1, entry 9), we then investigated the substrate scope for the insertion of fluoromethylcarbenes into the Si-H bond. As shown in Scheme 1, trialkylsilanes could be smoothly converted into the desired products in moderate to good yields (2a-2g). Severe steric effects would result in the complete suppression of Si-H bond insertion (2h). For a slightly hindered substrate, a moderate yield was obtained under slightly modified reaction conditions (2i). Phenylsilane showed a much lower reactivity

FeCI(TPP) (2 mol %) Na₂S₂O₄ (20 mol %) Ph₂S⁺CH₂R_F -OTf CsF (2.5 equiv.) R_F= CF₃, I DMA, rt. 2 h Rr = CF2H. II Et₃SiCH₂CF₃ Bu₃SiCH₂CF₃ ("C5H11)3SiCH2CF3 2b, 87%^a (86%)^b 2c, 83%^a (88%)^b 2a, 53%^a (83%)^b (ⁿC₅H₁₁)₂MeSiCH₂CF₃ ("C6H13)3SiCH2CF3 $(^{n}C_{8}H_{17})_{3}SiCH_{2}CF_{3}$ 2d, 89%^a (99%)^b 2e, 81%^a (78%)^b 2f, 74%^a (77%)^b $\mathsf{BnSi}(\mathsf{Me})_2\mathsf{CH}_2\mathsf{CF}_3 \quad {}^t\!\mathsf{BuSi}({}^i\!\mathsf{Pr})_2\mathsf{CH}_2\mathsf{CF}_3$ PhSi(Me)₂CH₂CF₃ 2g, 40%^a (53%)^b 2i, 44%^a (60%)^{bc} 2j, (50%)bc Bu₃SiCH₂CF₂H Et₃SiCH₂CF₂H $(^{n}C_{5}H_{11})_{3}SiCH_{2}CF_{2}H$ 2k, (82%)bd 21, 90%^a (75%)^{bd} 2m, 90%^a (70%)^{bd}

Scheme 1 Substrate scope for the insertion of methylcarbenes into the Si-H bond. ^a Isolated yields; ^b the yields in parentheses were determined by $^{19}\mathrm{F}$ NMR spectroscopy; $^{c}\mathrm{Cs_2CO_3}$ was used instead of CsF, toluene was used instead of DMA, and the reaction temperature was 80 °C; d Zn was used instead of Na₂S₂O₄ and DMF was used instead of DMA.

and the modified conditions gave the expected product in only 50% yield (2j). The product was so volatile that we failed to isolate it from the reaction solvent toluene. Besides trifluoromethylcarbene, difluoromethylcarbene could also be inserted well into the Si-H bond (2k-2m).

Organosilicon compounds are highly attractive scaffolds and have found widespread applications in organic synthesis, 10 materials chemistry, 11 and pharmaceuticals. 12 Si-H bond functionalization is one of the most straightforward protocols to synthesize organosilicon derivatives. This carbene insertion strategy is worth paying attention since it allows for the convenient formation of the Si-C bond and the incorporation of fluoromethyl groups.

Inert C-H bond functionalization is a challenging research area and a powerful tool for organic synthesis. 13 The insertion of fluoromethylcarbenes into the inert Csp3-H bond was also investigated. Although a large number of reaction conditions were screened, we could not identify optimal conditions to obtain a high yield (see the ESI†). Fortunately, we found that moderate yields could be obtained for the insertion of trifluoromethylcarbene into the benzyl C-H bond (Scheme 2, 4a-4b). For the alkyl C-H bond, the yield was quite low (4c). In these reactions, substrates 3 have to be used as the reaction solvent. Therefore, it was quite difficult to isolate the products from substrates 3 due to their similar polarity and the high volatility of products 4.

Phosphines are widely used in synthetic chemistry. For example, they can act as ligands in organometallic chemistry, 14 and as catalysts in the Morita-Baylis-Hillman reaction. 15 P-H functionalization is apparently an efficient strategy to prepare organophosphines. Trifluoromethylcarbene was found to be able to insert into the P-H bond to furnish the desired product in a moderate yield (Scheme 3).

Other X-H (X = N or S) bond insertions were also investigated. For the insertion into the N-H bond in arylamines such as 4-chlorophenylamine (4-ClC₆H₄NH₂), no desired product was produced. The S-H bond in thiophenol (PhSH) could react with sulfonium salt I to give sulfur ether (PhSCH₂CF₃). But the reaction may not proceed via trifluoromethylcarbene insertion into the S-H bond since thiophenol could act as a nucleophile to directly attack salt I under basic conditions.

Based on the above results and our previous observations, 9a,c we propose that the reaction may proceed through a concerted X-H insertion. The Fe-carbene (Fe=CHR_F, $R_F = CF_3$

Scheme 2 Insertion of trifluoromethylcarbene into the inert C-H bond. ^a The yields were determined by ¹⁹F NMR spectroscopy.

Scheme 3 Insertion of trifluoromethylcarbene into the P-H bond.

Scheme 4 The proposed transition state.

or CF₂H) generated *in situ* is highly reactive, and thus would be readily trapped by the X–H bond (Scheme 4). The cleavage of the X–H bond and the formation of C–H and C–X bonds would occur simultaneously to give the final products.

Conclusions

In conclusion, we have described the Fe-catalyzed insertion of fluoromethylcarbenes including trifluoromethylcarbene and difluoromethylcarbene into Si–H, C–H and P–H bonds. This work represents the first protocol for the insertion of difluoromethylcarbene into the Si–H bond, and the mild strategy for the insertion of fluoromethylcarbenes into X–H (X = Si, C and P) bonds. The fluoromethylcarbene insertion strategy may find synthetic utility in other research areas.

Conflict of interest

The authors declare no competing financial interest.

Acknowledgements

The authors thank the National Basic Research Program of China (2015CB931900, 2012CBA01200), the National Natural Science Foundation (21421002, 21472222, 21502214, 21672242), the Chinese Academy of Sciences (XDA02020105, XDA02020106), the Science and Technology Commission of Shanghai Municipality (15DZ1200102), the Key Research Program of Frontier Sciences (CAS) (QYZDJ-SSW-SLH049), and the Syngenta Ph.D. Fellowship awarded to Y. Duan for financial support.

Notes and references

(a) B. Morandi and E. M. Carreira, Angew. Chem., Int. Ed.,
 2010, 49, 938-941; (b) B. Morandi and E. M. Carreira,
 Angew. Chem., Int. Ed., 2010, 49, 4294-4296; (c) B. Morandi
 and E. M. Carreira, Angew. Chem., Int. Ed., 2011, 50, 9085-9088; (d) B. Morandi, J. Cheang and E. M. Carreira, Org.
 Lett., 2011, 13, 3080-3081; (e) B. Morandi, B. Mariampillai
 and E. M. Carreira, Angew. Chem., Int. Ed., 2011, 50, 1101-

- 1104; (f) Z. Chai, J.-P. Bouillon and D. Cahard, *Chem. Commun.*, 2012, 48, 9471–9473; (g) S. A. Kunzi, B. Morandi and E. M. Carreira, *Org. Lett.*, 2012, 14, 1900–1901; (h) C. B. Liu, W. Meng, F. Li, S. Wang, J. Nie and J.-A. Ma, *Angew. Chem., Int. Ed.*, 2012, 51, 6227–6230; (i) H. Luo, G. Wu, Y. Zhang and J. Wang, *Angew. Chem., Int. Ed.*, 2015, 54, 14503–14507; (j) S. Hyde, J. Veliks, B. Liegault, D. Grassi, M. Taillefer and V. Gouverneur, *Angew. Chem., Int. Ed.*, 2016, 55, 3785–3789.
- 2 (a) K. J. Hock, L. Mertens and R. M. Koenigs, *Chem. Commun.*, 2016, 52, 13783–13786; (b) L. Mertens, K. J. Hock and R. M. Koenigs, *Chem. Eur. J.*, 2016, 22, 9542–9545.
- 3 (a) S. Purser, P. R. Moore, S. Swallow and V. Gouverneur, Chem. Soc. Rev., 2008, 37, 320–330; (b) I. Ojima, Fluorine in Medicinal Chemistry and Chemical Biology, John Wiley & Sons Ltd, United Kingdom, 2009; (c) X.-L. Qiu, X. Yue and F.-L. Qing, in Chiral Drugs: Chemistry and Biological Action, ed. G.-Q. Lin, Q.-D. You and J.-F. Cheng, John Wiley & Sons, Inc., Hoboken, New Jersey, 2011, pp. 195–252; (d) J. Wang, M. Sanchez-Rosello, J. L. Acena, C. Del Pozo, A. E. Sorochinsky, S. Fustero, V. A. Soloshonok and H. Liu, Chem. Rev., 2013, 114, 2432–2506; (e) Y. Zhou, J. Wang, Z. Gu, S. Wang, W. Zhu, J. L. Aceña, V. A. Soloshonok, K. Izawa and H. Liu, Chem. Rev., 2016, 116, 422–518.
- 4 (a) K. Herd, in *Organofluorine Chemistry*, Springer, 1994, pp. 287–314; (b) M. Matsui, *J. Fluorine Chem.*, 1999, 96, 65–69; (c) A. Sikder and N. Sikder, *J. Hazard. Mater.*, 2004, 112, 1–15.
- 5 (a) Y. Landais and D. Planchenault, Tetrahedron Lett., 1994, 35, 4565-4568; (b) F. Z. Dorwald, Metal Carbenes in Organic Synthesis, WILEY-VCH Verlag GmbH, Weinheim (Federal Republic of Germany), 1999; (c) G. Bertrand, Carbene Chemistry-From fleeting intermediate to powerful reagents, Marcel Dekker, Inc., 2002; (d) H. M. L. Davies and R. E. J. Beckwith, Chem. Rev., 2003, 103, 2861-2903; (e) M. P. Doyle, R. Duffy, M. Ratnikov and L. Zhou, Chem. Rev., 2010, 110, 704-724; (f) S.-F. Zhu and Q.-L. Zhou, Acc. Chem. Res., 2012, 45, 1365-1377; (g) R. A. Moss and M. P. Doyle, Contemporary carbene chemistry, John Wiley & Sons, Inc., Hoboken, New Jersey, 2014.
- 6 (a) B. Morandi and E. M. Carreira, Org. Lett., 2011, 13, 5984–5985; (b) G. A. Molander and L. N. Cavalcanti, Org. Lett., 2013, 15, 3166–3169; (c) G. Wu, Y. Deng, C. Wu, X. Wang, Y. Zhang and J. Wang, Eur. J. Org. Chem., 2014, 4477–4481; (d) Z. Chen, Y. Zheng and J.-A. Ma, Angew. Chem., Int. Ed., 2017, 56, 4569–4574.
- 7 (a) P. K. Mykhailiuk, Angew. Chem., Int. Ed., 2015, 54, 6558–6561; (b) J. Li, X.-L. Yu, J. Cossy, S.-Y. Lv, H.-L. Zhang, F. Su, P. K. Mykhailiuk and Y. Wu, Eur. J. Org. Chem., 2017, 266–270.
- 8 (a) J. Zheng, J. Cai, J. H. Lin, Y. Guo and J. C. Xiao, Chem. Commun., 2013, 49, 7513–7515; (b) J. Zheng, J. H. Lin, J. Cai and J. C. Xiao, Chem. Eur. J., 2013, 19, 15261–15266; (c) X.-Y. Deng, J.-H. Lin, J. Zheng and J.-C. Xiao, Chem. Commun., 2015, 51, 8805–8808; (d) J. Zheng, J.-H. Lin, L.-Y. Yu, Y. Wei, X. Zheng and J.-C. Xiao, Org. Lett., 2015, 17, 6150–6153; (e) J. Zheng, L. Wang, J.-H. Lin, J.-C. Xiao

- and S. H. Liang, *Angew. Chem., Int. Ed.*, 2015, **54**, 13236–13240; (*f*) X. Y. Deng, J. H. Lin and J. C. Xiao, *Org. Lett.*, 2016, **18**, 4384–4387; (*g*) J. Zheng, R. Cheng, J.-H. Lin, D.-H. Yu, L. Ma, L. Jia, L. Zhang, L. Wang, J.-C. Xiao and S. H. Liang, *Angew. Chem., Int. Ed.*, 2017, **56**, 3196–3200.
- (a) Y. Duan, J. H. Lin, J. C. Xiao and Y. C. Gu, Org. Lett.,
 2016, 18, 2471–2474; (b) C.-B. Yue, J.-H. Lin, J. Cai,
 C.-P. Zhang, G. Zhao, J.-C. Xiao and H. Li, RSC Adv., 2016,
 35705–35708; (c) Y. Duan, J. H. Lin, J. C. Xiao and
 Y. C. Gu, Chem. Commun., 2017, 53, 3870–3873.
- 10 (a) M. Bois and T. Skrydstrup, Chem. Rev., 1995, 95, 1253–1277; (b) S. E. Denmark and R. F. Sweis, Acc. Chem. Res., 2002, 35, 835–846; (c) J. W. Kennedy and D. G. Hall, Angew. Chem., Int. Ed., 2003, 42, 4732–4739.
- 11 (a) M. A. Brook, Silicon in organic, organometallic, and polymer chemistry, J. Wiley, 2000; (b) F. Hoffmann, M. Cornelius, J. Morell and M. Froba, Angew. Chem., Int. Ed., 2006, 45, 3216–3251.
- 12 S. Fujii and Y. Hashimoto, *Future Med. Chem.*, 2017, 9, 485–505.
- (a) J.-Q. Yu and Z. Shi, CH activation, Springer, 2010;
 (b) O. Baudoin, Chem. Soc. Rev., 2011, 40, 4902-4911;
 (c) B. G. Hashiguchi, S. M. Bischof, M. M. Konnick and R. A. Periana, Acc. Chem. Res., 2012, 45, 885-898;
 (d) C. Cheng and J. F. Hartwig, Chem. Rev., 2015, 115, 8946-8975;
 (e) W. Liu and J. T. Groves, Acc. Chem. Res., 2015, 48, 1727-1735;
 (f) L. Yang and H. Huang, Chem. Rev., 2015, 115, 3468-3517;
 (g) T. Kang, Y. Kim, D. Lee, Z. Wang and S. Chang, J. Am. Chem. Soc., 2014, 136, 4141-4144;
 (h) X. Wu, Y. Zhao and H. Ge, J. Am. Chem. Soc., 2014, 136, 1789-1792;
 (i) K. Liao, S. Negretti, D. G. Musaev, J. Bacsa and H. M. L. Davies, Nature, 2016, 533, 230-234;
 (j) S. Mukherjee, B. Maji, A. Tlahuext-Aca and F. Glorius, J. Am. Chem. Soc., 2016, 138, 16200-16203.
- 14 (a) C. A. Tolman, *Chem. Rev.*, 1977, 77, 313–348; (b) T. Hayashi, *Acc. Chem. Res.*, 2000, 33, 354–362.
- 15 (a) Y. L. Shi and M. Shi, Adv. Synth. Catal., 2007, 349, 2129–2135; (b) Y. Wei and M. Shi, Acc. Chem. Res., 2010, 43, 1005–1018; (c) Y. Wei and M. Shi, Chem. Rev., 2013, 113, 6659–6690.